

AMENDMENTS TO THE SPECIFICATION:

Please amend paragraph 49 as follows:

[0049] Next, the anti-reflection coating A thus processed will be compared to a conventional anti-reflection coating B disclosed in Japanese Journal of Applied Physics, column 36, page L52 to L54, published in 1997. The conventional coating B has two layers of titanium oxide and aluminum oxide on the first facet 3a ~~3b~~ of the device chip 71, which are formed by the ion-assisted evaporation technique. The thickness of the first layer 7a, titanium oxide layer, is about 100nm and that of the second layer 7b, aluminum oxide layer, is formed on the titanium oxide layer with a thickness of 185nm. The thickness of the first layer 7a and that of the second layer 7b are determined such that the reflectivity thereof becomes nearly 0% at 1,550nm. Clearly, the total thickness of the structure A is thinner than that of the structure B.